

# Supporting Information

## Decreasing reflection through the mutually positive effects of nanograss and nanopillars

C. H. Lin,<sup>a,b</sup> J. Shieh,<sup>\*c</sup> C. C. Liang,<sup>a</sup> C. C. Cheng<sup>d</sup> and Y. C. Chen<sup>e</sup>

<sup>a</sup> Department of Photonics, National Cheng Kung University, Tainan, Taiwan.

<sup>b</sup> Advanced Optoelectronic Technology Center, National Cheng Kung University, Tainan, Taiwan.

<sup>c</sup> Department of Materials Science and Engineering, National United University, Miaoli, Taiwan. E-mail: jshieh@nuu.edu.tw

<sup>d</sup> Department of Physics, National Central University, Taoyuan, Taiwan.

<sup>e</sup> Department of Electrical Engineering, Chung Hua University, Hsinchu, Taiwan.

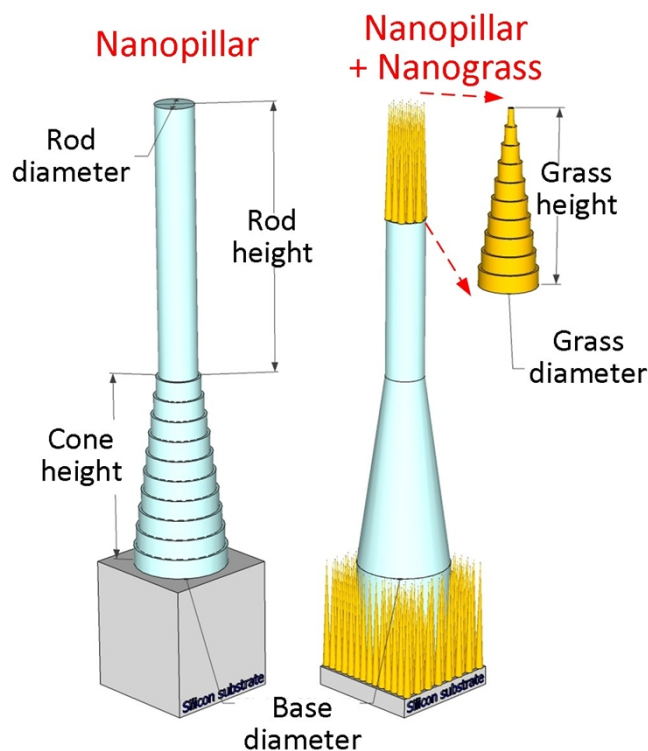


Fig. S1. The illustrated geometry of the RCWA configuration.

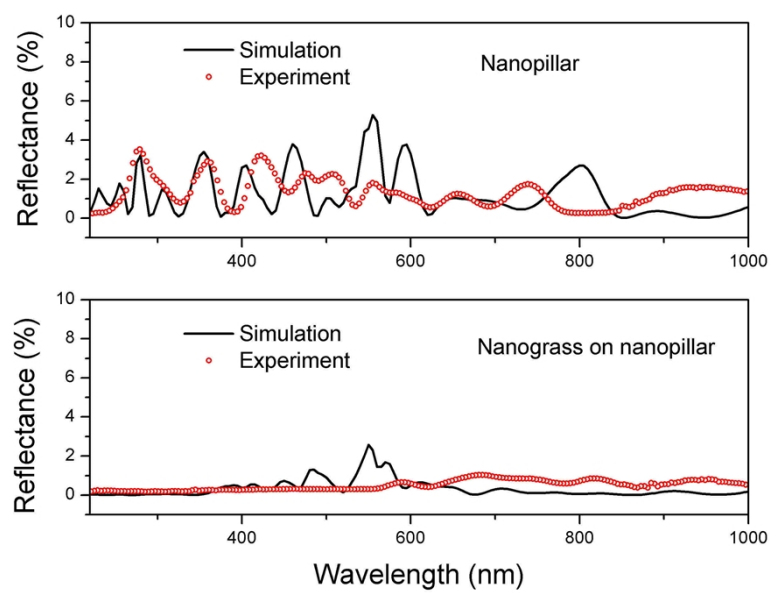


Fig. S2. The overlays of measured and simulated results of specular reflections at normal incidence.

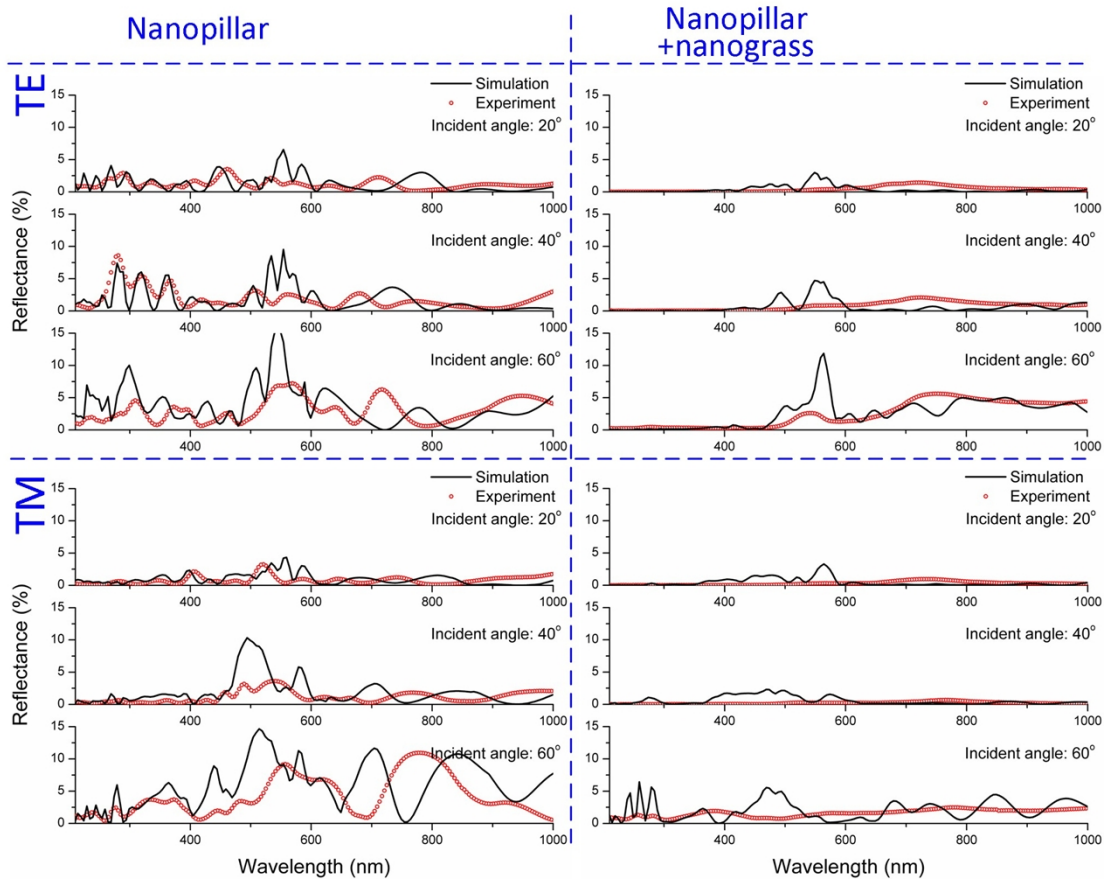


Fig. S3. The overlays of measured and simulated results of specular reflections at incident angles of 20°, 40°, and 60° for both TE and TM polarizations.